WEE, wafer edge expose
LHP, lo temp hot plate
CPL, chill plate
CHP, chilling hot plate
ADH, HMDS dispense and hot plate
UNC, unicassette station
PRA, the main robot
IRA, interface robot
CRA, Cassette stage robot
CWH, cup wash
DEV, developer
COT, coater
TCT, top coater
SBU, stationary buffer
EIS, wafer handoff to the stepper
TCP, transition chill plate
TRS, transition station
PUP, engineering cassette station